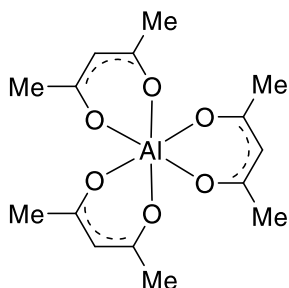


Catalog # 93-1302 Aluminum acetylacetonate, 98%



## Thermal Behavior:

- Melting point: 192-193°C
- Boiling point (dec): 320°C
- Sublimation: 150°/1 Torr
- TGA diagram and data are available in [1]

## Technical Notes:

1. Precursor and dopant for thin aluminum film deposition.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
LaAl <sub>x</sub> O <sub>y</sub>	ALD CVD	125°C 95-105°C	1.5-2.25 Torr 3.8 Torr	La(thd) <sub>3</sub> , O <sub>3</sub> La(thd) <sub>3</sub> , O <sub>2</sub>	325-400°C 400-800°C	2 3
α-(Al <sub>x</sub> Ga <sub>1-x</sub> ) <sub>2</sub> O <sub>3</sub>	CVD	HCl:H <sub>2</sub> O sol	AP	Ga(acac) <sub>3</sub>	400°C	4
Al <sub>1-x</sub> Ti <sub>x</sub> O <sub>y</sub>	CVD	MeOH:H <sub>2</sub> O sol	AP	Ti(acac) <sub>4</sub>	550°C	5

## References:

1. [Surf. Coat. Technol. 2007, 201, 9055.](#)
2. [J. Mater. Chem. 2001, 11, 2340.](#)
3. [Appl. Phys. Lett. 2003, 83, 3540.](#)
4. [AIP Advances 2020, 10, 115019.](#)
5. [J. Appl. Phys. 2022, 131, 105301.](#)